

Remarks

Claim 19 has been amended with the details set forth in Attachment I (Version with Markings to Show Changes).

The 35 USC 103 Rejections

Claims 19, 21-26 and 29 are rejected under 35 USC 103(a) as unpatentable over Russo et al in view of Chrisey et al. Parent Claim 19 sets forth "means for controlling the environment of the deposition chamber" which may be very broadly considered as the gas entrance port 24 and/or the evacuation port 26 of Russo et al. Claim 19 has been amended to set forth "means for controlling the composition of the deposit" by a group of three ways for carrying out the control. These features are not taught or suggested by either Russo et al or Chrisey et al. Thus, this rejection should be withdrawn.

Claims 20, 27, 28 and 30 are rejected under 35 USC 103(a) as unpatentable over Russo et al and Chrisey et al, and further in view of Moto et al. These claims depend from Claim 19 which has been amended to set forth features not taught or suggested by Russo et al or Chrisey et al, as discussed above. Moto et al fails to teach the features lacking in the primary and secondary reference. Also, where in any of these three references is there found "means for processing the face of the substrate" as set forth in Claim 20. Thus, aside from these reference failing to teach the rotational speeds set forth 27 or 28, and the energy fluence of Claim 30, as well as the limitation of Claim 20, the features added to parent Claim 19 are also not taught thereby. Thus, this ground of rejection should be withdrawn.

Conclusion

In view of the amendments to these claims, and the foregoing comments, each rejection is believed to have been overcome. Thus, this application is in condition for allowance based on Claims 19-30.

Date: 6/26/2001

Enclosure:

Attachment I

Version with Markings to
Show Changes Made

Respectfully submitted,



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Attachment I
S.N. 09/636,134
Version with Markings to Show Changes Made

In the Claims:

Claim 19, amend to read as follows:

19. (Amended) An apparatus for depositing a low work function material on a substrate by laser ablation using short-wavelength photons, including:

- a deposition chamber,
- a target containing low work function material in said chamber,
- a laser capable of directing short-wavelength photons into said chamber and onto said target,
- means for rotating said target,
- means for controlling the composition of the deposit by controlling at least one of the group consisting of the environment of said deposition chamber, the target composition, and the target temperature,
- a substrate located in said chamber,
- means for holding said substrate, and
- means for at least rotating said substrate.